Safety
- The PECVD is normally run at temperatures up to 400 C and uses pyrophoric, toxic, and oxidizing gases.
- Buddy (does not need to be PECVD trained) required for after hour usage
- User is required to be in the lab during operation.

Process Restrictions
Material Restrictions
- Silicon Wafers only, no resists, no glass substrates, limited metals with staff approval
- Standard 4" and 6" wafer thickness only, please see machine manager for other sample thickness and types.

Parameter Restrictions
- Only run standard recipes.
- Do not modify or change any of the recipes without staff approval first.

Scheduling / Sign-up Restrictions
- 8 AM to 6 PM normal daytime hours
- No reservation of blocks greater than 3 hrs during 8 - 6PM weekday daytime hours, no time restrictions outside daytime hours.

Requirements (Do Every Time)
- Users are required to run the proper clean time in each recipe as well as the final auto clean process for each use.
- Place system in PROPER standby state (see instructions)!

Prohibitions (Never Do)

Common Problems

| Problem: Wafer not unloaded/stuck in chamber | Root Cause: System was reset during operation, wafer slid on chuck | Solution: Call machine manager |

Other Comments or Cautions